

PATENT
MIC04 P-106

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Examiner : George A. Goudreau
Group : 1763
Confirmation No. : 4253
Applicant : Imad Mahawili, PhD
Serial No. : 09/488,309
Filed : January 20, 2000
For : REACTOR WITH REMOTE PLASMA SYSTEM AND
METHOD OF PROCESSING A SEMICONDUCTOR
SUBSTRATE

Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

RESPONSE

In response to the Office Action mailed June 19, 2002, having a three-month period of response ending September 19, 2002, Applicant wishes to amend his application as follows:

IN THE CLAIMS:

Please cancel Claims 1, 4, 7, 10, 16, 32, 57, 59-61, and 64-77. Please amend Claims 2, 5, 6, 8, 9, 11, 15, 17, 20, 22, 24, 33, 34, 35, 37-55, 58, 62, and 63 as follows:

C1 2. The reactor according to Claim 22, further comprising a heater for selectively heating the substrate in said processing chamber.

C2 5. The reactor according to Claim 22, wherein said plasma generator generates an electromagnetic field, said electromagnetic field for ionizing the gas into a gas plasma.

6. The reactor according to Claim 22, wherein said plasma generator ionizes said gas exteriorly of said processing chamber to isolate the substrate from said electromagnetic field.

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